Semitool ST-2700 SRD Operation

Upper SRD unit is dedicated to 100mm (4”) substrates and the lower to 150mm (6”).

1) Place wafers into a clean Teflon cassette that fits inside the chamber.
2) Turn ON the N2 switch for the appropriate unit. N2 control unit is atop the upper SRD unit.
3) Open SRD main control compartment door located below the bottom unit. Lift and turn the compartment knobs and pull top of door out towards operator.
   a) Locate controller for the SRD unit of interest, i.e. upper or lower, and turn the power ON for that controller.
   b) Wait approximately 30s for the control unit readout to indicate 0.
   c) Set Rinse time / Dry time. A minimum dry time of 240s is recommended.
   d) Do not change the spin speeds!
   e) Ensure Resistivity Monitor switch is on MANUAL.
   f) The Rinse RPM should be set at 600 and the Dry RPM should be 1200.
4) Place cassette with the H-bar facing into chamber back and close chamber door.
5) Press the green START button to initiate processing.
6) Make sure the RINSE rpm is about 600 and the DRY rpm reads around 1200.
7) Once the process is complete, remove wafers, close chamber door, push in the control compartment, and turn off the N2 switch.

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Revision	Description of change	Change initiator(s)	Date
1	Update Layout	James Bohlman	3-10-2025